Photolithography Wafer Spinners

Manager: Edward Camacho
Backup: Garry Bordonaro
Backup: 254-4853, 254-4936

Safety
- Face shields must be worn at ALL TIMES
- No materials outside hoods unless in vented waste

Process Restrictions

Material Restrictions
- NO WATER in spinners unless posted
- NO unapproved solvents in spinners (see list)
- NO biomaterials

Parameter Restrictions
- None

Scheduling / Sign-up Restrictions
- No scheduling at this time
- 15 min. time limit when busy

Requirements (Do Every Time)
- Use proper spin size chuck - SMALLER than substrate
- Empty pipettes before disposal
- Clean up - NOTHING left in hood

Prohibitions (Never Do)
- NEVER strip materials other than photoresist
- NEVER Use water in spinners
- NEVER Put contaminated material in non-vented trash can
- NEVER Spray solvent on spinner chuck - WIPE to clean

Common Problems

<table>
<thead>
<tr>
<th>Problem:</th>
<th>Root Cause:</th>
<th>Solution:</th>
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</thead>
<tbody>
<tr>
<td>Vacuum interlock failed</td>
<td>Chuck not seated or dirty, wafer back dirty</td>
<td>Check chuck mounting, clean chuck, clean wafer back</td>
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<tr>
<td>Poor resist uniformity</td>
<td>Poor wafer surface, contaminated spin bowl</td>
<td>Clean or replace wafers, clean spin bowl, adjust spin parameters</td>
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Other Comments or Cautions
- Do not strip wafers in spinners
- Keep spin bowls clean

Calls to staff phones will be automatically forwarded to their cell phones during accessible hours. At other times leave a message or send them an email.